

Wearable applications featuring photonic on-chip sensors are on the rise.

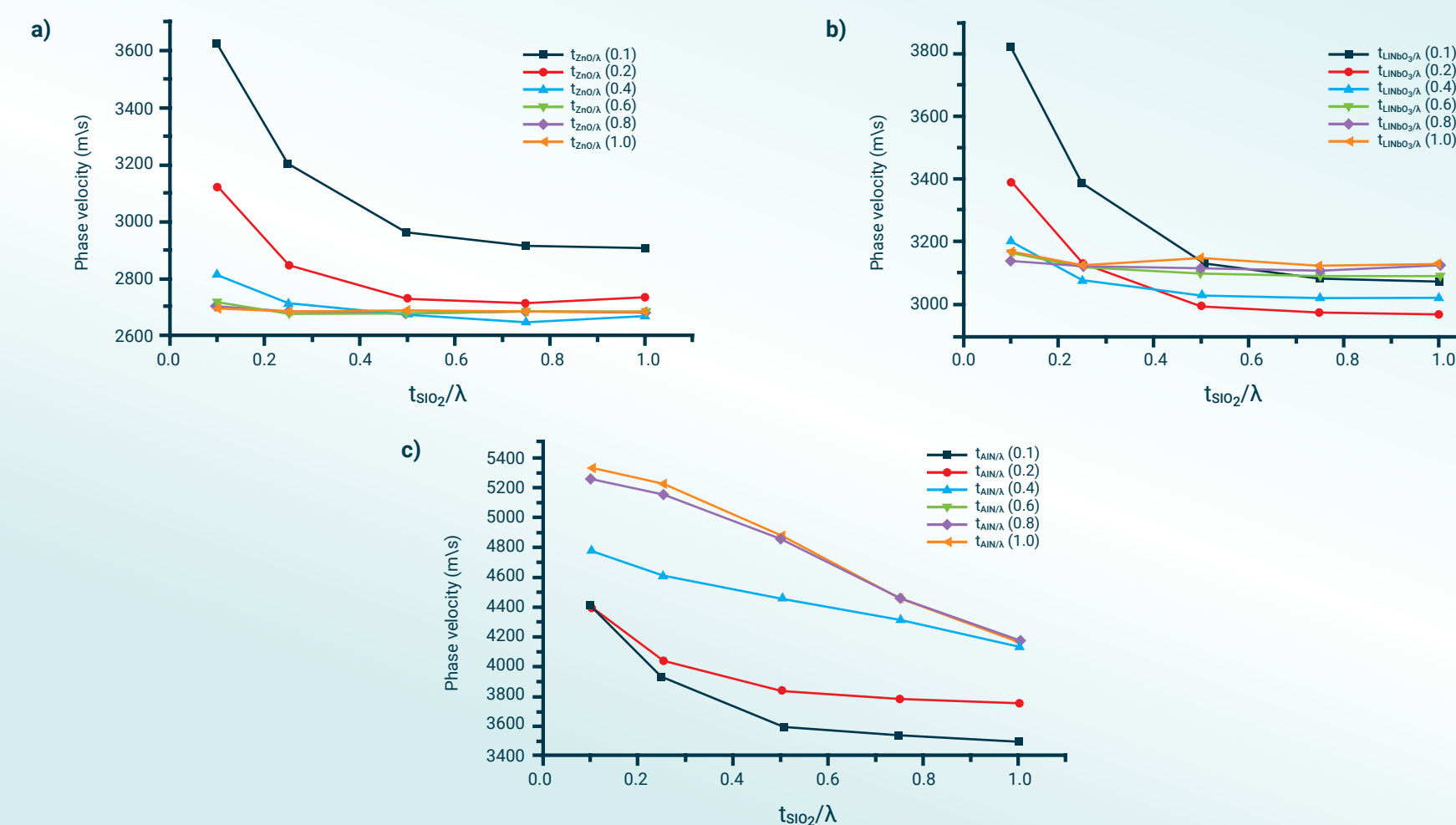


The acousto-optic technique is seen to be popular in modulation or control of optic signals in optic devices.

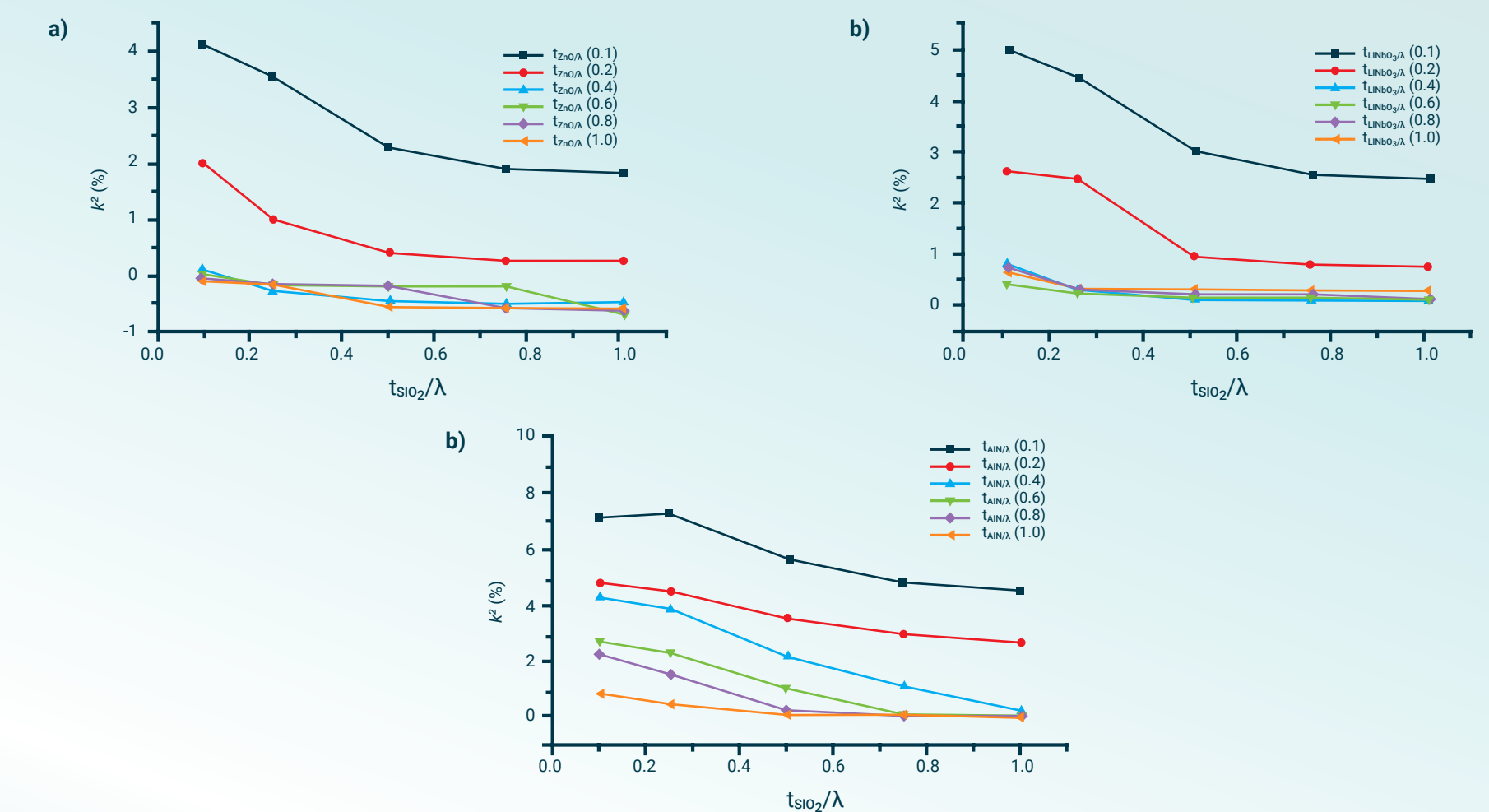


Study of different multilayer structures is carried out to fabricate an efficient acousto-optic device with high figure of merit.

## FINDINGS:



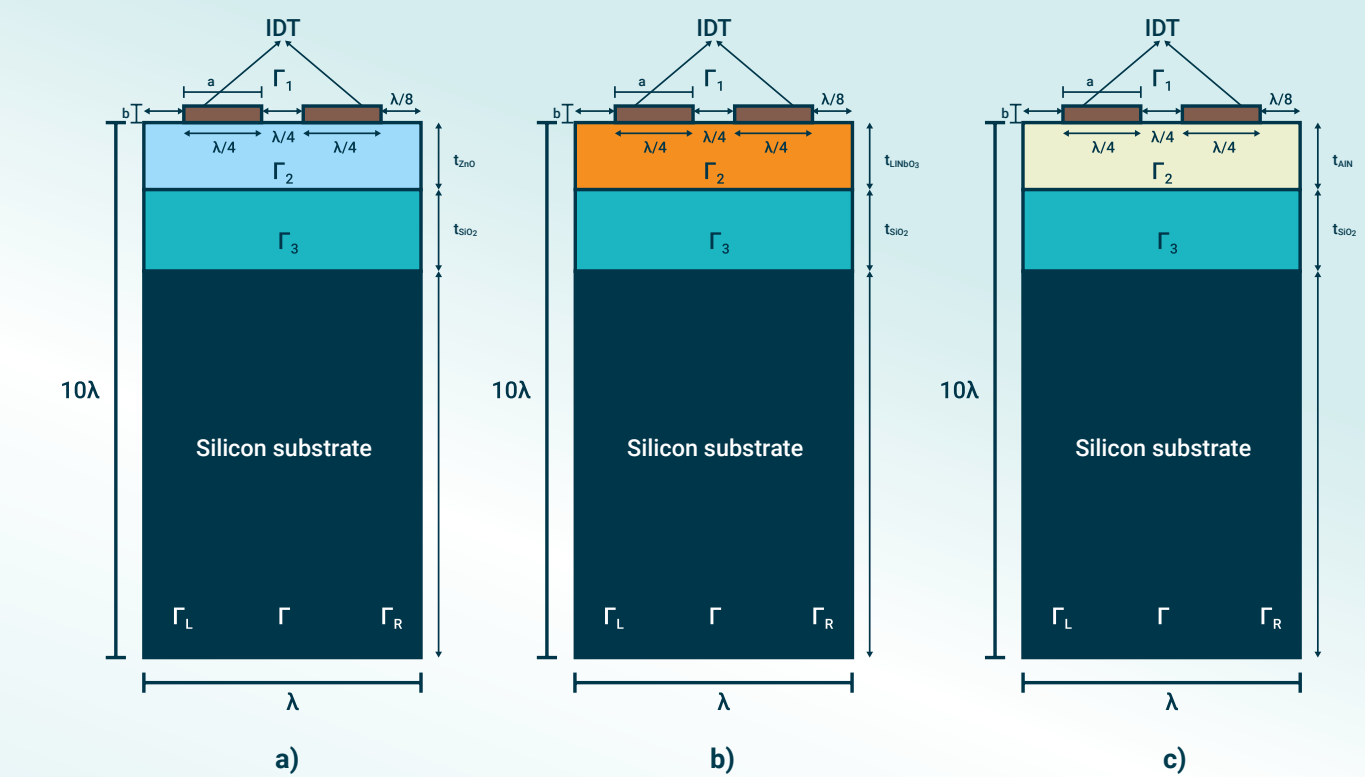
Phase velocity versus normalised thickness of SiO<sub>2</sub> on different normalised thicknesses of (a) ZnO (b) LiNbO<sub>3</sub> (c) AlN.



Electromechanical coupling coefficient ( $k^2$ ) versus normalised thickness of SiO<sub>2</sub> on different normalised thicknesses of (a) ZnO (b) LiNbO<sub>3</sub> (c) AlN.

## CONCLUSIONS:

It is found that the AlN/SiO<sub>2</sub>/Si multilayer structure gave the highest  $k^2$ , i.e., 7.15 at the normalised thickness of  $0.1\lambda$  (for SiO<sub>2</sub> and AlN layer). It also has the highest acousto-optic figure of merit, i.e.,  $7.04 \times 10^{-14} \text{ s}^3/\text{kg}$  (which is also higher than the AOFM of individual bulk materials used in this study). Hence, it is concluded that by using an AlN/SiO<sub>2</sub>/Si multilayer structure, a high acousto-optic figure of merit can be achieved, which is not possible by using any choice of single bulk material. Moreover, it makes it possible to realise lab-on-chip applications using AlN/SiO<sub>2</sub>/Si structure, which is a CMOS compatible SAW structure.



A two-dimensional unit cell geometry used in FEM simulation for the multilayer structure (a) (ZnO/SiO<sub>2</sub>/Si), (b) (LiNbO<sub>3</sub>/SiO<sub>2</sub>/Si) and (c) (AlN/SiO<sub>2</sub>/Si).